

REMARKS/ARGUMENTS

The amendments to the specification further amplify the description of the target source as claimed. No new matter has been added, as the amplified description was fully disclosed in the originally filed specification and claims and as illustrated in the drawings. For example, The revised claims are believed to overcome all of the Examiner's rejections of the claims on the bases of 35 USC 112, 102(b) and 103(a). Independent Claims 1 and 8 now recite that the target source is made of two parts of the same deposition material and together form a cohesive target source. The remaining claims add further distinctions over the prior art.

Applicants submit the invention set forth in the revised claims is patentable for the foregoing reasons that both target source parts are made of the same deposition material and (2) they form a cohesive target. These claimed features when taken together result in a product and method that prevents contamination of the layer(s) being deposited, firstly by not exposing the ion beam environment to other materials such as an exposed target holder or an additional deposition source made of a material other than the intended deposition material, and secondly by preventing migration of bonding or other support materials foreign to the intended inertness of the foreign materials. Whether taken alone or in combination, none of the cited prior art, including the cited references to Hunt et al (US 5,674,367), Nakamura et al (JP 61-067768), Fukushima et al (JP 63-143258) and Ivanov et al (US 5,522,535), nor any other prior art known to applicants, anticipate or make obvious the invention as now claimed with the above described features. The very simplicity of the invention in a well established art, combined with the unexpected results both by eliminating the possibility of contamination, from the target source assembly, of the deposited layer(s) in highly sensitive ion beam deposition of costly materials and by significant cost savings in target replacement are clear evidence of patentable invention.